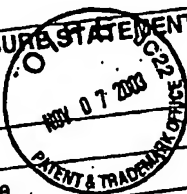


U.S. Department of Commerce, Patent and Trademark Office (PTO Form 1449 modified)		Docket No. AMAT/6392/DSM/LO W K/JW	Serial No. 10/010,950
SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT BY APPLICANT		Applicant Xia, et al.	Confirmation No.: 5694
(Use several sheets if necessary)		Filing Date November 13, 2001	Group 2818
Examiner Dung Anh Le			



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*Examiner Initial		Document Number	Issue Date	Applicant(s) Name	Class	Subclass	Filing Date if Appropriate
<i>de</i>	A1	6,465,366	10/15/2002	Nemani, et al.	438	778	09/12/2000
	A2	5,926,740	07/20/1999	Forbes, et al.	438	763	10/27/1997
	A3	5,876,891	03/02/1999	Takimoto, et al.	430	71	05/26/1995
	A4	5,710,067	01/20/1998	Foots, et al.	437	238	06/07/1995
	A5	5,638,251	06/10/1997	Goel, et al.	361	313	10/03/1995
	A6	5,607,773	03/04/1997	Ahlburn, et al.	428	427	12/20/1994
	A7	5,494,712	02/27/1996	Hu, et al.	427	589	11/17/1997
	A8	5,465,680	11/14/1995	Loboda	117	84	07/01/1993
	A9	5,242,530	09/07/1993	Batey, et al.	156	613	08/05/1991
	A10	5,224,441	07/06/1993	Felts, et al.	118	718	09/27/1991
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	A12	4,759,947	07/26/1988	Ishihara, et al.	427	38	10/04/1985
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A13		4,532,150						
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de	B1	09-008031	01/10/1997	JP	H01L	21/316	<input type="checkbox"/>	<input checked="" type="checkbox"/>
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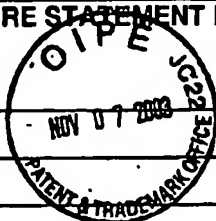
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*Examiner Initial	Including Author, Title, Date, Pertinent Pages, Etc.	
<i>de</i>	C1	U.S. Patent Application No. 09/270,039, filed on March 16, 1999.
	C2	Written Opinion from PCT/US99/22424, dated April 5, 2001.
	C3	PCT Partial International Search Report for US99/22317 dated March 21, 2000.
		Date Considered <i>Mar-2004</i>

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	A2	2003/0129827	07/10/2003	Lee, et al.	438	629	07/15/2002
	A3	2003/0111730	06/19/2003	Takeda, et al.	257	758	05/28/2001
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	A5	2003/0003765	01/02/2003	Gibson, Jr. et al.	438	760	01/02/2002
	A6	2003/0001282	01/02/2003	Meynen, et al.	257	777	06/25/2002
	A7	2002/0111042	08/15/2002	Yau, et al.	438	789	11/15/2001
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	A10						
	A11						

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Dle	C4	PCT International Search Report for US99/22425 dated February 11, 2000.
	C5	Dijkstra, et al. "Optimization of Anti-Reflection Layers for Deep UV Lithography", Proceeding of SPIE Optica/Laser Microlithography, Bellingham, SPIE, Volume 1674, (1992) Pages 362-375.
	C6	Omar, M.A. "Elementary Solid State Physics: Principles and Applications," Lowell Technological Institute, Addison-Wesley Publishing Company, 1975, Pages 124 & 125.
	C7	Fukuda, et al. "Highly Reliable SiOF Film Formation by ECR-CVD using SiF ₂ H ₂ ", (1996) Symposium on VLSI Technology Digest of Technical Papers, IEEE, Pages 114-115.
	C8	PCT International Search Report for US/02/40034, dated May 19, 2003.
Dle	C9	Wu, et al, "Advanced Metal Barrier Free Cu Damascene Interconnects with PECVD Silicon Carbide Barriers for 90/65-nm BEOL Technology", 2002 IEEE Pages 595-598.

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	A2	6,054,379	04/25/2000	Yau, et al.	438	623	02/11/1998
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	A13						

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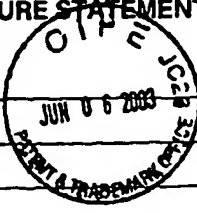
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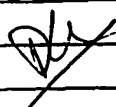
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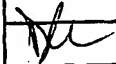
*Examiner Initial		Including Author, Title, Date, Pertinent Pages, Etc.
<i>Dle</i>	C1	PCT International Search Report for US/02/36229 dated 09/03/2003 (AMAT/6392.PC)
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Examiner	<i>Dle</i>	Date Considered Mar-2004

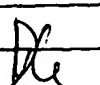
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Examiner Dung Anh Le					



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	A2	6,500,773	12/31/2002	Gaillard, et al.	438	790	11/27/2000
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	A4						
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	C1	
	C2	
	C3	
Examiner 		Date Considered 3/2004

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